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Atomic Layer Deposition and Atomic Layer Etching

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Message from the Guest Editors

Dear Colleagues,

In recent years, there have been significant advances in atomic layer deposition (ALD) and atomic layer etching (ALE), which are very powerful and elegant tools in many industrial and research applications. As ALD/ALE technology matures and diversifies, it is believed to create various applications through innovation and optimization. This Special Issue of *Materials* on "Atomic Layer Deposition and Atomic Layer Etching" is intended to cover original research and critical review articles on recent advances in all aspects of ALD/ALE.

Potential topics include but are not limited to the following:

- ALD applications: memory, display, energy, and emerging applications, etc.;
- ALD fundamentals: precursors and chemistry, growth, and characterization;
- Area-selective ALD and epitaxial growth of ALD;
- In situ characterization of ALD processes and materials;
- Thermal and plasma atomic layer etching (ALE).

Prof. Dr. Jiyoung Kim Prof. Dr. Si Joon Kim *Guest Editors*







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Message from the Editor-in-Chief

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